

PR-89-036



August 27, 2001

Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572  
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Subject:

Serial No. 09/919,036 09/21/00

Chun-Hong Peng, Rex Chen,  
Simon Chang

AN INTELLIGENT WET ETCHING TOOL AS  
A FUNCTION OF CHEMICAL CONCENTRATION,  
TEMPERATURE AND FILM LOSS

Grp. Art Unit: 2812

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#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 6,004,881 to Bozada et al., "Digital Wet  
Etching of Semiconductor Materials, discloses a wet chemical  
digital etching technique for gallium arsenide or other  
semiconductor materials.

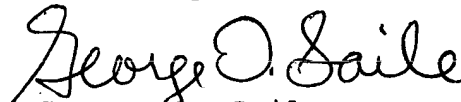
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U.S. Patent 5,582,746 to Barbee et al, "Real Time Measurement of Etch Rate During a Chemical Etching Process", teaches a contactless method and apparatus for real-time in-situ monitoring of a chemical etching process during etching of at least one wafer in a wet chemical etchant bath.

Sincerely,

  
George O. Saile,  
Reg. No. 19572

Order Number (Optional)

PR-89-036

Application Number

09/919,036

Lyfðeoni!

Applicant: Chun-Hong Peng et al.

FBling Date

09/21/00

Group 11 Unit

2812

U. S. PATENT DOCUMENTS

A circular stamp from the Intellectual Property Office (IPO). The text "O I P O" is at the top, "AUG 27 2001" is in the center, and "PATENT & TRADE MARK OFFICE" is at the bottom. The stamp is divided vertically by a line.

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## FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Portion, Pages, Etc.)

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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.